



Docket No. 50261-2

#5/B
VB
11/8/01

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

APPLICANT: G. Taylor et al.
SERIAL NO.: 09/330,418 EXAMINER: S. Lee
FILED: June 11, 1999 GROUP: 1752
FOR: NOVEL POLYMERS AND PHOTORESIST COMPOSITIONS

THE HONORABLE COMMISSIONER OF PATENTS AND TRADEMARKS
WASHINGTON, DC 20231

SIR:

AMENDMENT

Applicants are in receipt of the Office Action dated June 20, 2000 for the above identified application. Please amend the application as follows.

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JUN 27 2001
TECHNICAL ROOM

IN THE CLAIMS

Please cancel claims 1-8 and 14-18 without prejudice.

Please add the following new claims.

19. A positive-acting photoresist composition comprising a photoacid generator compound and a polymer that is substantially free of aromatic groups and that comprises pendant acid-labile groups that contain an optionally substituted cycloalkyl group having 3 or 4 ring carbon atoms, or an optionally substituted alkenyl group.

20. A photoresist composition of claim 19 wherein the polymer comprises pendant acid-labile groups that contain an optionally substituted alkenyl group.